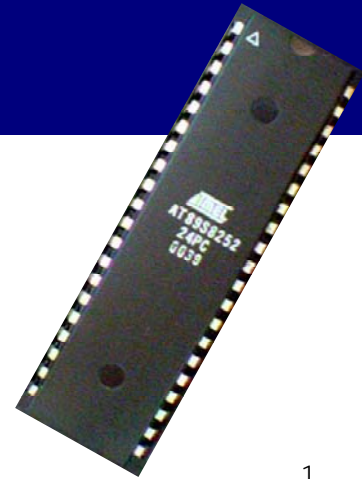


Digital Integrated Circuits & Microcontrollers

Chapter 5. Semiconductor Memories



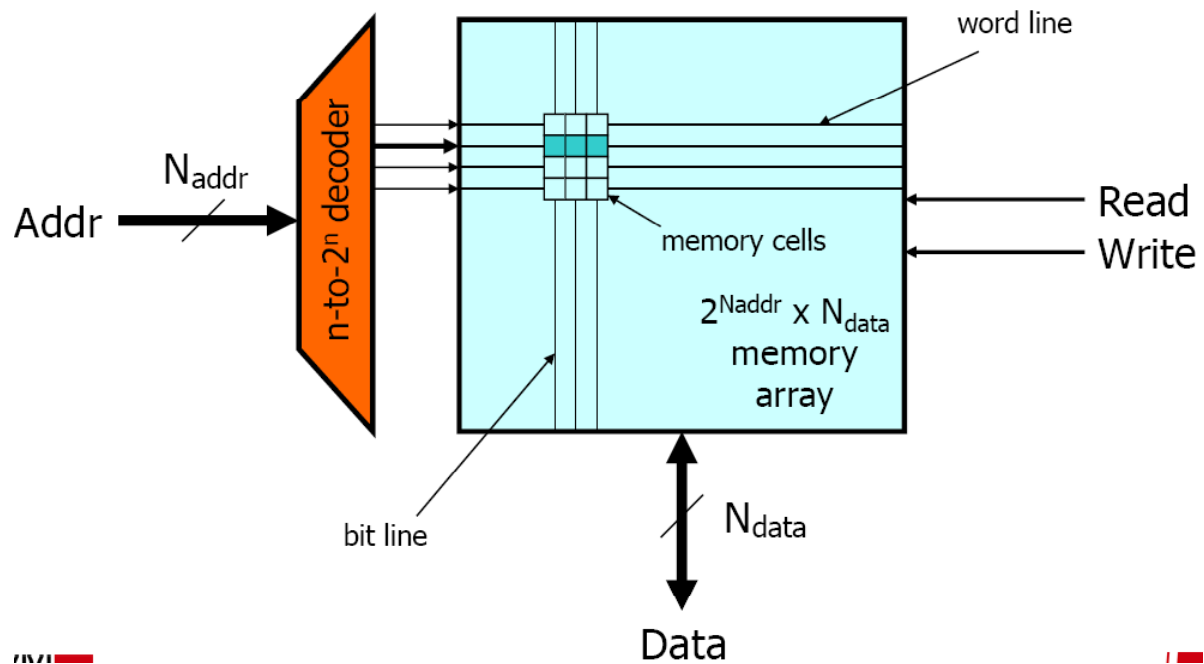
1

Memories

- Bits of information arranged into arrays
 - Each row is an item of information and is identified by an **Address**
 - The set of bits identified by the same address belong to a **Word**
- The number of addresses is often a power of two;
- The number of bits in a word is sometimes a multiple of four or eight, or arbitrary

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Memory organization



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Memory Basics

- **RAM: Random Access Memory**
 - historically defined as memory array with individual bit access
 - refers to memory with both Read and Write capabilities
- **ROM: Read Only Memory**
 - no capabilities for “online” memory Write operations
 - Write typically requires high voltages or erasing by UV light

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Memory Basics

■ Volatility of Memory

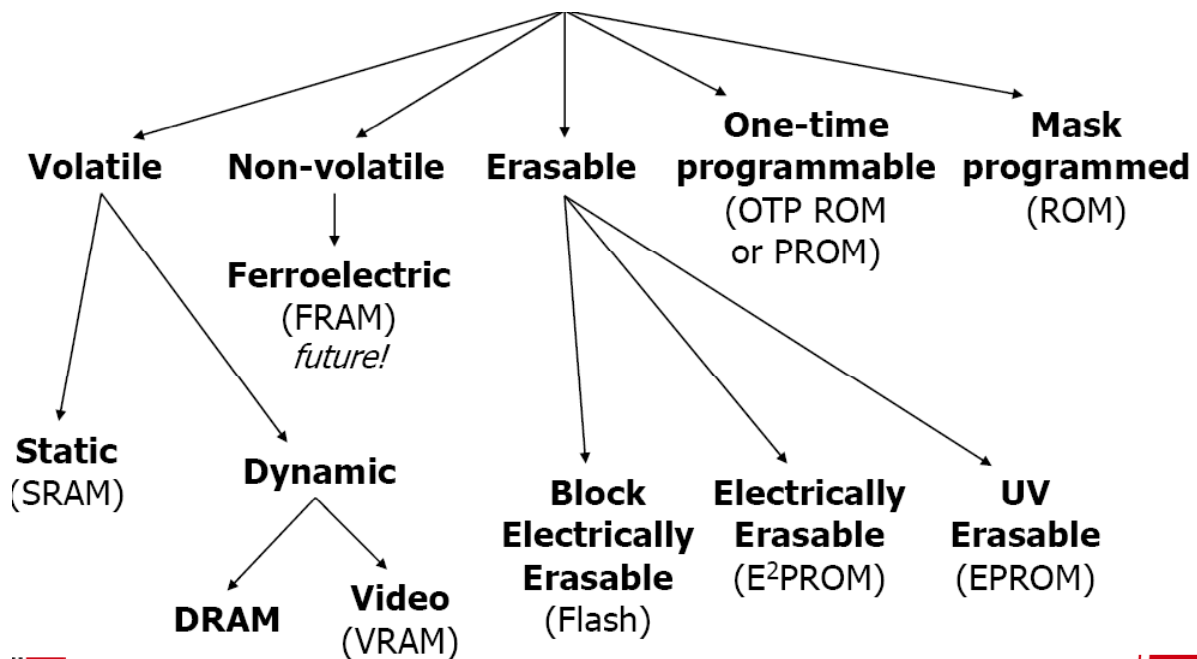
- volatile memory loses data over time or when power is removed
 - RAM is volatile
- non volatile memory stores data even when power is removed
 - ROM is non-volatile

■ Static vs. Dynamic Memory

- Static: holds data as long as power is applied (SRAM)
- Dynamic: will lose data unless refreshed periodically (DRAM)

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Memory Types



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ROM: Read Only Memory

- Nonvolatile memories
- Only can access data, cannot to modify data
- Lower cost: used for permanent memory in printers, fax, and game machines, and ID cards
- Typical applications:
 - store the microcoded instructions set of a microprocessor
 - store a portion of the operation system for PCs
 - store the fixed programs for microcontrollers (firmware)

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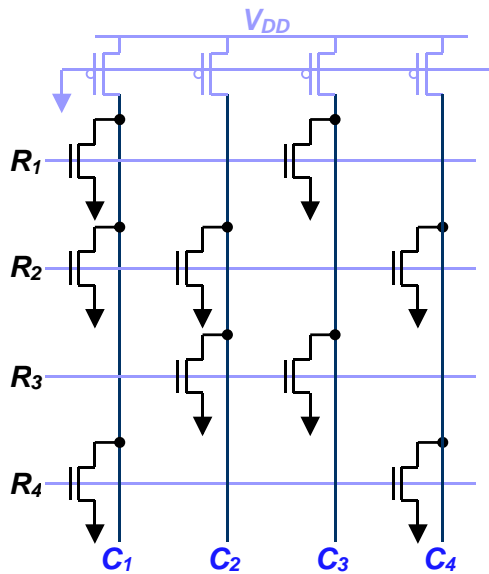


ROM: Read Only Memory

- PROM: Programmable Read Only Memory
 - programmable by user -using special program tools/modes
 - read only memory -during normal use
 - non-volatile
 - Read Operation
 - like any ROM: address bits select output bit combinations
 - Write Operation
 - typically requires high voltage (~15V) control inputs to set data
 - Erase Operation
 - EPROM: erasable PROM: uses UV light to reset all bits
 - EEPROM: electrically-erasable PROM, erase with control voltage

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4bit × 4Bit NOR-based ROM Array



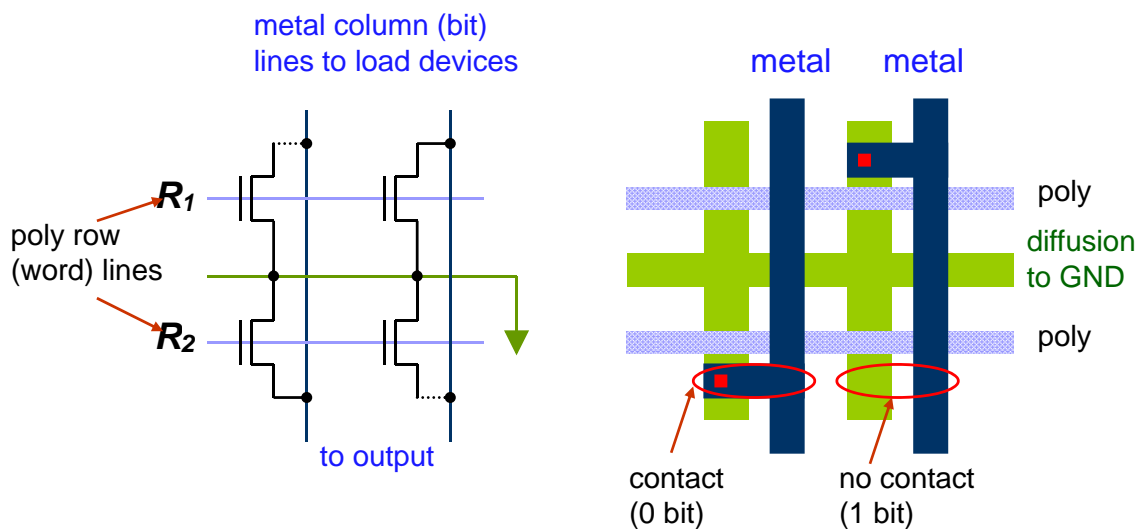
- "1" bit stored - absence of an active transistor
- "0" bit stored - presence of an active transistor

R_1	R_2	R_3	R_4	C_1	C_2	C_3	C_4
1	0	0	0	0	1	0	1
0	1	0	0	0	0	1	1
0	0	1	0	1	0	0	1
0	0	0	1	0	1	1	0

A word is selected by rising to "1" the corresponding wordline

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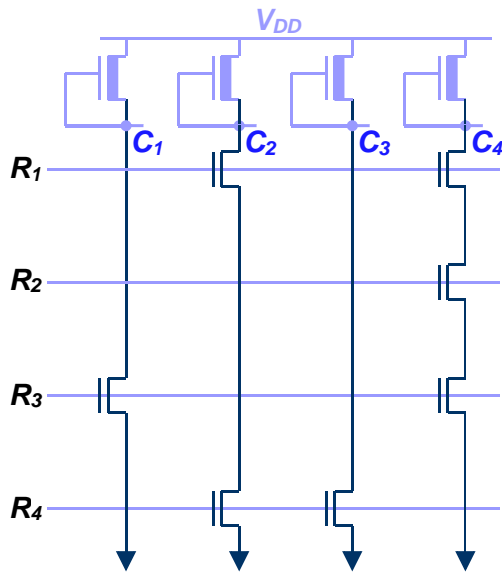
Contact-Mask Programmable NOR ROM



- "0" bit: drain is connected to metal line via a metal-to-diffusion contact
- "1" bit: omission the connect between drain and metal line.

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4Bit × 4Bit NAND-based ROM Array



- “1” bit stored - presence of a transistor that can be switched off
- “0” bit stored - shorted / normally-on transistor

R_1	R_2	R_3	R_4	C_1	C_2	C_3	C_4
0	1	1	1	0	1	0	1
1	0	1	1	0	0	1	1
1	1	0	1	1	0	0	1
1	1	1	0	0	1	1	0

A word is selected by putting to “0” the corresponding wordline R_i

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Nonvolatile Read-Write Memories

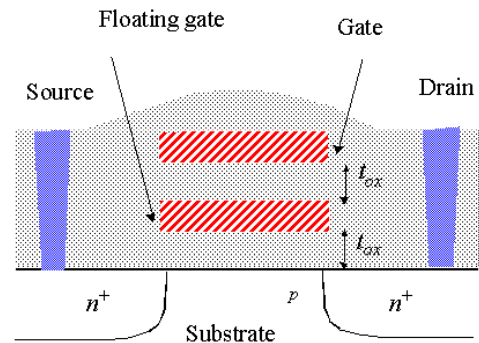
- The architecture is similar to the ROM structure
 - Array of transistors placed on a word-line/bit-line grid
 - Special transistor that permits its threshold to be altered electrically
 - Programming: selectively disabling or enabling some of these transistors
 - Reprogramming: erasing the old threshold values and start a new programming cycle

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EPROM

■ The floating gate avalanche-injection MOS (FAMOS) transistor:

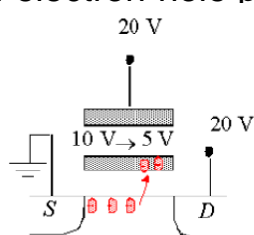
- extra polysilicon strip is inserted between the gate and the channel - **floating gate**
- impact: double the gate oxide thickness, reduce the transconductance, increase the threshold voltage
- threshold voltage is programmable by the trapping electrons on the floating gate through avalanche injection



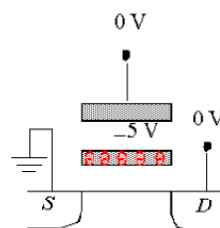
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EPROM

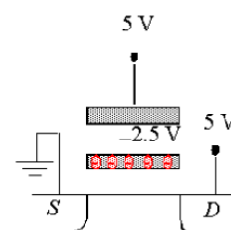
- Electrons acquire sufficient energy to become “hot” and traverse the first oxide insulator so that they get trapped on the floating gate
- Electron accumulation on the floating gate is a self-limiting process that increases the threshold voltage (~7V)
- The trapped charge can be stored for many years
- The erasure is performed by shining strong ultraviolet light on the cells through a transparent window in the package
- The UV radiation renders the oxide conductive by direct generation of electron-hole pairs



Avalanche injection



Removing programming voltage leaves charge trapped



Programming results in higher V_T

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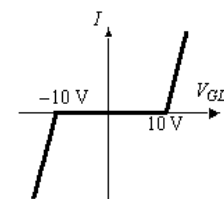
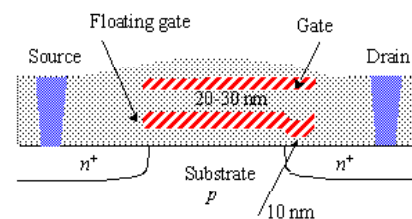
EPROM

- The erasure process is slow (~min.)
- The erasure procedure is **off-system!**
- Programming takes several usecs/word
- Limited endurance - max 1000 erase/program cycles
- The cell is very simple and dense: large memories at low cost!
- Applications that do not require regular reprogramming

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EEPROM

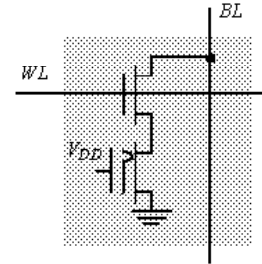
- Provide an electrical-erasure procedure
- Modified floating-gate device, floating-gate tunneling oxide (**FLOTOX**):
- reduce the distance between floating gate and channel near the drain
- Fowler-Nordheim tunneling mechanism (when apply 10V over the thin insulator)



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EEPROM

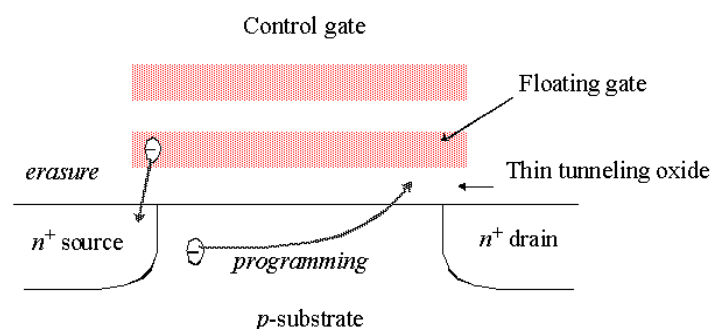
- Reversible programming by reversing the applied voltage (rise and lower the threshold voltage)
 - difficult to control the threshold voltage
 - extra transistor required as access device
- Larger area than EPROM
- More expensive technology than EPROM
- Offers a higher versatility than EPROM
- Can support 10⁵ erase/write cycles



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Flash Memories

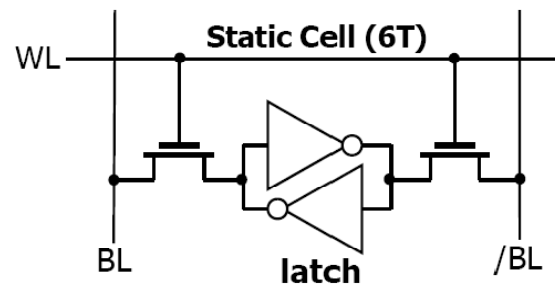
- Combines the density of the EPROM with the versatility of EEPROM structures
 - Programming: avalanche hot-electron-injection
 - Erasure: Fowler-Nordheim tunneling (like EEPROM)
 - Difference: erasure is performed in bulk for the complete (or subsection of) memory chip



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Static RAM (SRAM)

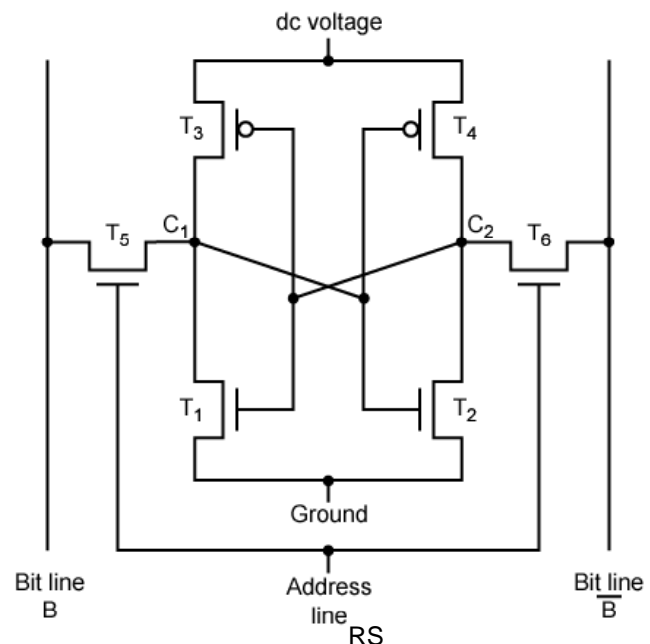
- Permit the modification (writing) of stored data bits
- The stored data can be retained infinitely, without need of any refresh operation
- 3 Operation States: hold, write, read
- Basic 6T (6 transistor) SRAM Cell
 - bistable (cross-coupled) INVs for storage
 - 2 access transistors
 - word line, WL, controls access
 - WL = 0 (hold)
 - WL = 1 (read/write)



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The basic operations on SRAM cells

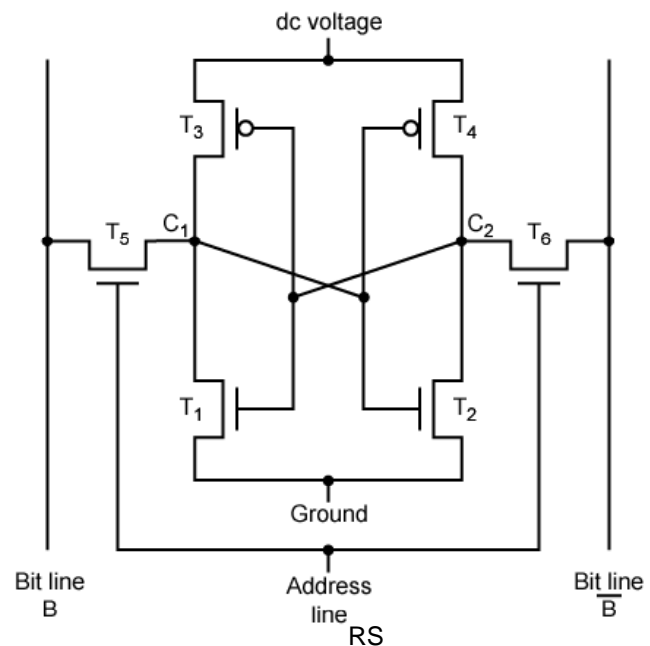
- RS = 0 (T_5, T_6 off)
 - data is being held
- RS = 1 (T_5, T_6 on)
 - Write "1"
 - V_{B1} - forced to 0 by data write,
 - V_{C2} decreases to 0,
 - T_1 off; V_{C1} increases;
 - Final state: $V_{C1} = 1, V_{C2} = 0$
 - Read "1"
 - T_1 off; T_2 on;
 - V_{B1} pulled down,
 - $V_B > V_{B1}$ read as a logic "1"



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The basic operations on SRAM cells

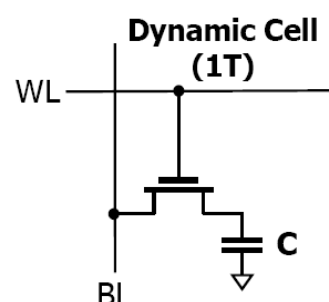
- $RS = 1$ (T_5, T_6 on)
 - Write "0"
 - V_B - forced to 0 by data write,
 - V_{C1} decreases to 0,
 - T_2 off; V_{C2} increases to 1;
 - Final state: $V_{C1} = 0, V_{C2} = 1$
 - Read "0"
 - T_1 on; T_2 off;
 - V_B pulled down,
 - $V_B < V_{B1}$ read as a logic "0"



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Dynamic Random Access Memory (DRAM)

- Dynamic: must be refreshed periodically
- Volatile: loses data when power is removed
- 1T DRAM Cell
 - single access transistor;
 - storage capacitor
- control input:
 - word line (WL);
 - data I/O: bit line (BL)



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